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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. 10/071,425
Filing Date February 8, 2002
Inventor Terry L. Gilton et al.
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner Thanhha S. Pham
Attorney Docket No. MI22-1828
Customer No. 021567
Title: Semiconductor Processing Method Using Photoresist and Antireflective
Coating

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

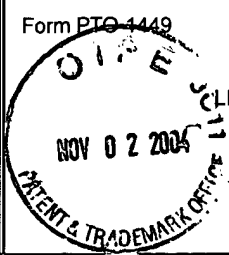
References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. Copies of the cited prior art references are attached. No admission is made regarding whether all the listed references are prior art.

Respectfully submitted,

Dated: 11-1-04

By: 
Mark S. Matkin
Reg. No. 32,268

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| Form PTO 4449  | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | ATTY. DOCKET NO. M122-1828 | | SERIAL NO. 10/071,425 | |
| LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) | | | | APPLICANT: Terry L. Gilton et al. | | | |
| | | | | FILING DATE February 8, 2002 | | GROUP 2813 | |

| U.S. PATENT DOCUMENTS | | | | | | | |
|-----------------------|-----------------|------|------|-------|----------|----------------------------|--|
| *Examiner's Initials | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | |
| | AA | | | | | | |
| | AB | | | | | | |
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| FOREIGN PATENT DOCUMENTS | | | | | | | | |
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| Document Number | Date | Country | Class | Subclass | Translation | | | |
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| | AL | | | | | | | |

| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | |
|---|--|--|
| AM | | Lee et al., <i>Lithographic Properties of SiN_x and Se₇₅Ge₂₅ Thin Films as the Low-Energy Ion-Beam Resist</i> , 5 th International Conference on Properties and Applications of Dielectric Materials, Seoul, Korea (May 25-30, 1997) pp. 635-638. |
| AN | | |
| AO | | |
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| EXAMINER | | DATE CONSIDERED |

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.